

An Advanced Asymmetric Supercapacitor Based on a Novel Ternary Graphene/Nickel/Nickel Oxide and Porous Carbon Electrodes with Superior Electrochemical Performance

*Miaomiao Liu, Jie Chang, Yang Bai, Jing Sun**

*The State Key Lab of High Performance Ceramics and Superfine Microstructure,
Shanghai Institute of Ceramics, Chinese Academy of Sciences, 1295 Ding Xi Road,
Shanghai 200050, China*

E-mail address: jingsun@mail.sic.ac.cn (J. Sun)

Tel: +86-12-52414301. Fax: +86-21-52413122

Electronic Supplementary Information (ESI)

Supplementary Graphics

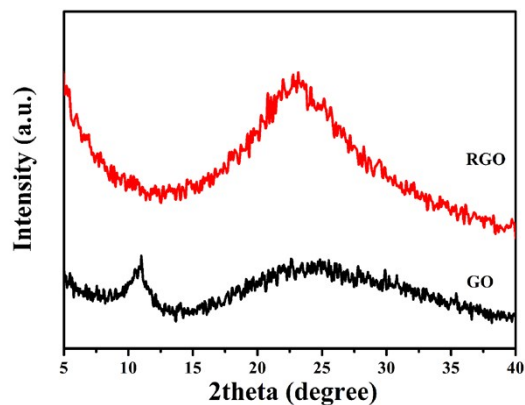


Fig. S1 XRD patterns of RGO and GO.

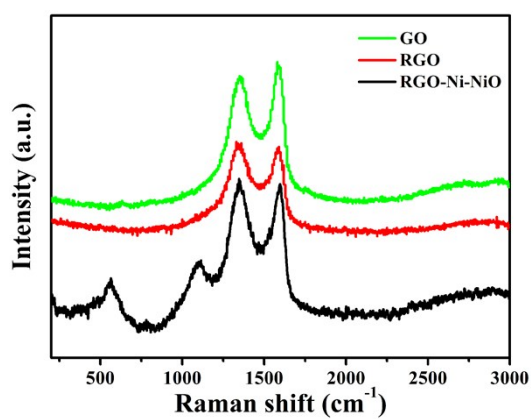


Fig. S2 Raman spectra patterns of GO, RGO and RGO/Ni/NiO.

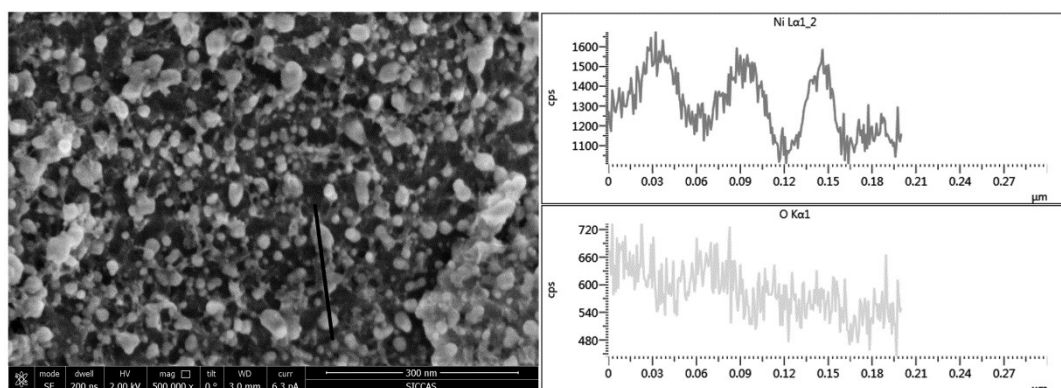


Fig. S3 Line scanning images of RGO/Ni/NiO.

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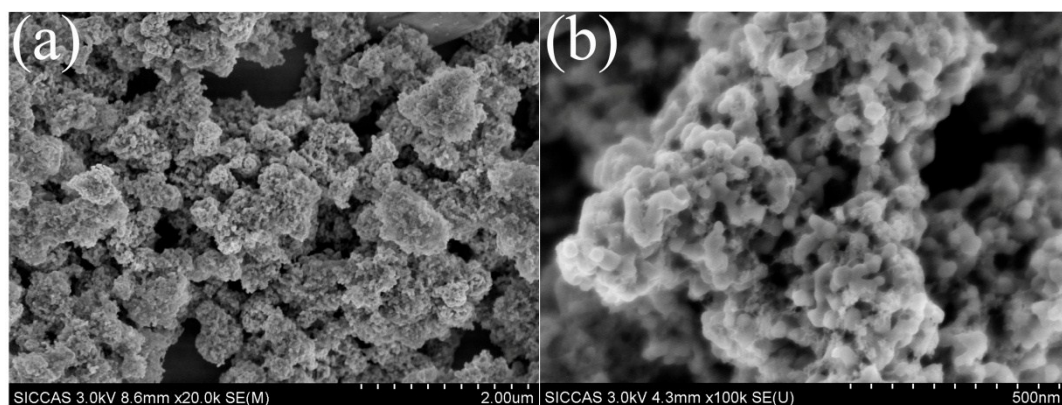


Fig. S4 SEM images of Ni/NiO.

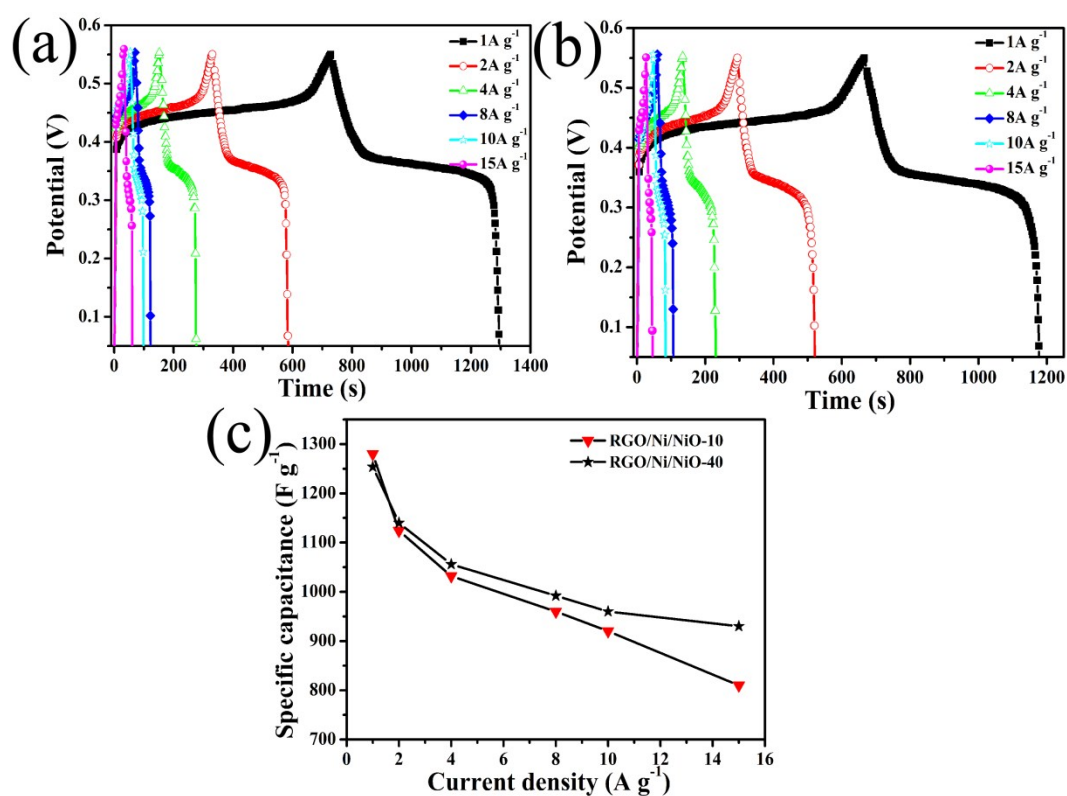


Fig. S5 Galvanostatic charge/discharge curves of (a) RGO/Ni/NiO-10 (b) RGO/Ni/NiO-40 at

different current densities. (c) Average specific capacitance at different current densities.

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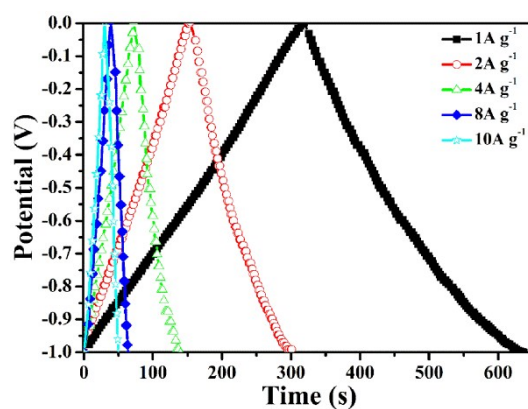


Fig. S6 Galvanostatic charge/discharge curves of PC at different current densities.

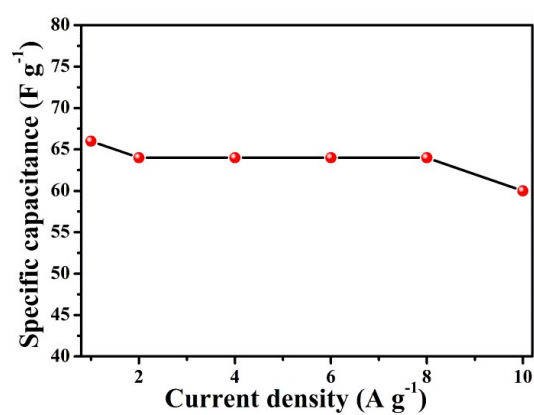


Fig. S7 Specific capacitance of PC//PC symmetry capacitor within a voltage window of 1 V at different current densities.